

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|-------|------|---|---|------------------|---------|------------------|
| L1 | 1855 | (438/706.ccls. or 438/710.ccls. or 438/714.ccls. or 438/725.ccls. or 438/745.ccls. or 438/963.ccls.) and ((remov\$3 with (etch\$3 near2 residue\$1)) or (remov\$3 with (photoresist or resist))) and plasma | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2005/07/05 17:14 |
| L2 | 38 | L1 and (charged adj particle\$1) and radical\$1 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2005/07/05 17:15 |